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(54) TREATMENT SYSTEM AND CORROSION RESISTANT MEMBER USED THEREFOR

(57) Abstract:

PROBLEM TO BE SOLVED: To provide a treatment system in which the problem of the corrosion of the inner wall of a treatment vessel is hard to occur and moreover to provide a corrosion resistant member excellent in plasma resistance and corrosion gas resistance and used for the treatment system.

SOLUTION: In a treatment system having a chamber 11 housing a wafer W as the substrate to be treated, a bell jar 12 provided in the upper direction of the chamber 11, a coil 65 as an antenna member for forming the induction electromagnetic field in the bell jar 12, a high frequency power source 66 applying high frequency electric power on the coil 65 and a gas feeding mechanism 40 feeding treatment gas, and in which plasma is formed by the induction electromagnetic field formed in the bell jar 12, and the wafer W is treated, as to the bell jar 12, the inner wall is composed of a film 14 containing a compound of the group 3a elements in the Periodic Table.

